



Maximizing GaN Power Transistor Performance with Embedded Packaging

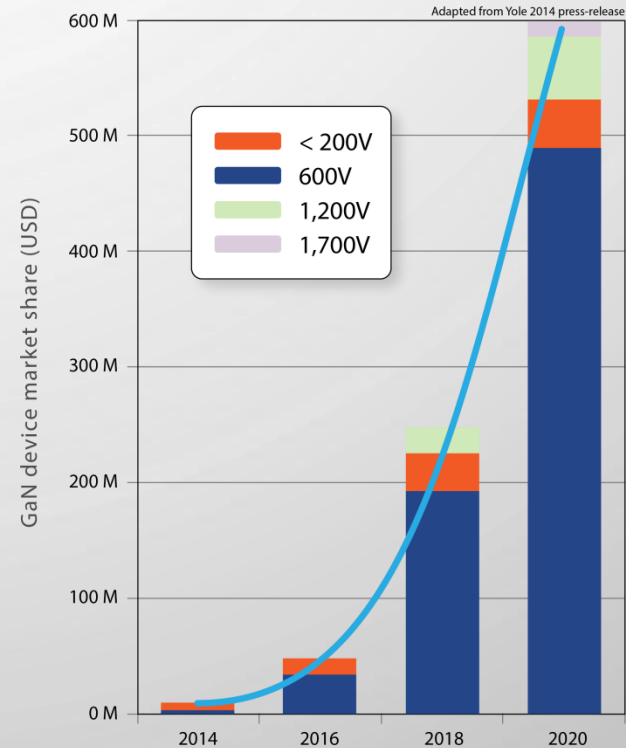
J. Roberts, CTO

GaN Systems, Inc.

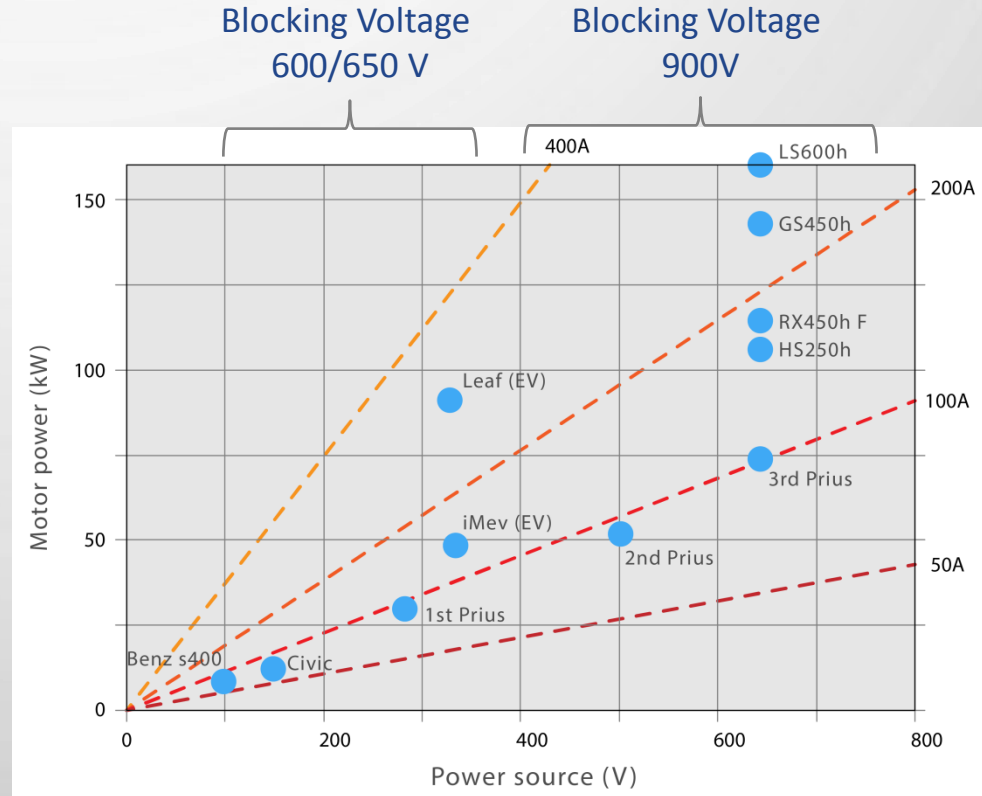
1145 Innovation Drive, Ottawa, ON, Canada

Market opportunities for GaN power transistors

- Very rapid sales growth is expected within the next five years leading to sales exceeding \$500M by 2020
- Yole has published a market research report and press releases (June 2014) that identifies EV/HEV applications as being a key element of the market opportunity
- According to Yole the "*Ramp-up will be quite impressive starting in 2016, at an estimated 80% CAGR*"

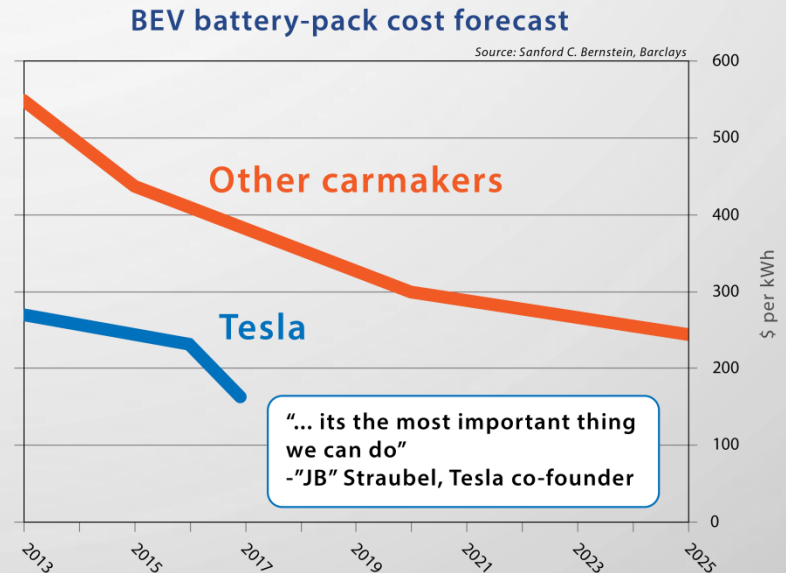
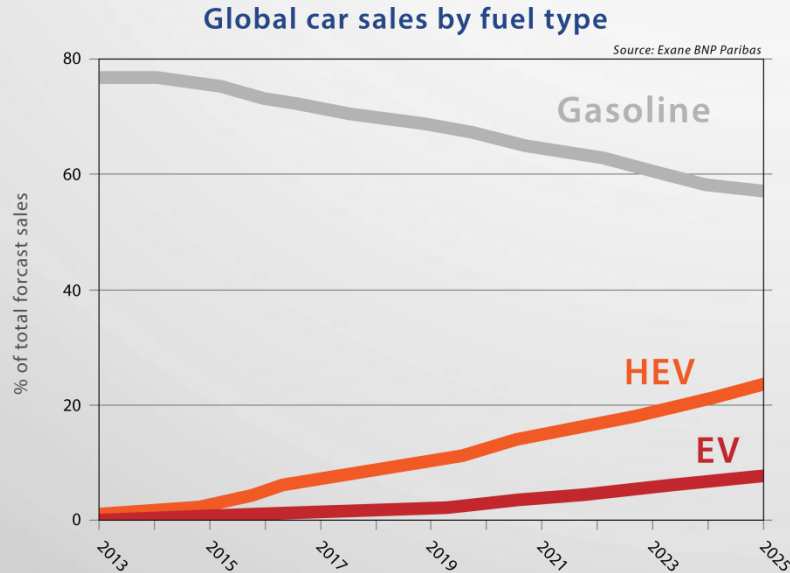


- 650 and 900 V devices are required by 2 level inverters
- IGBT devices currently used
- SiC and GaN are regarded as potential replacements
- 650 V GaN – 3 level inverter, high performance, low-cost, the best choice for 900 V operation at present
- 900 V SiC MOSFETs will be expensive and are difficult to protect and drive
- IGBTs too inefficient

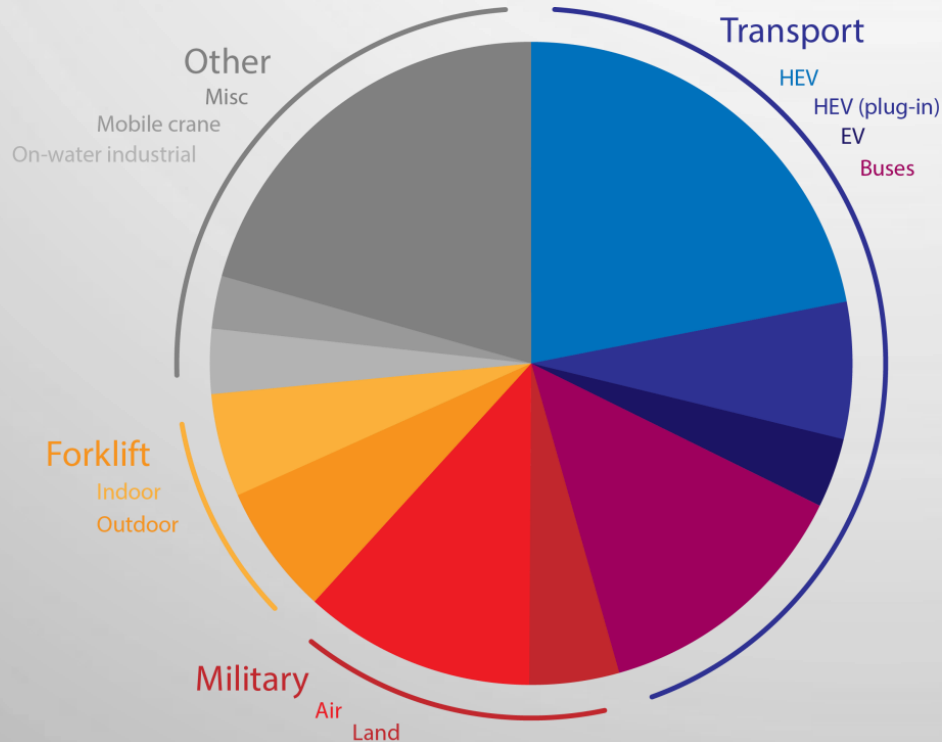


T. Kachi, et al "GaN Power device and Reliability for Automotive Applications"
Reliability physics Symposium (iRPS) 2012.J.

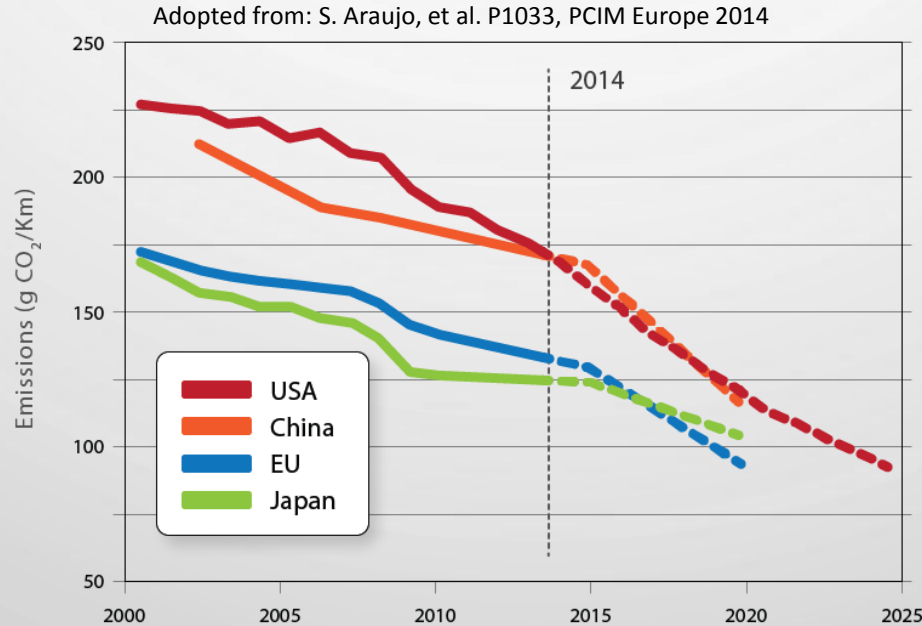
Annual Production 30 Million EV/HEV Cars by 2025



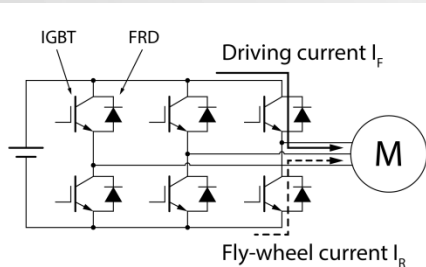
- Battery costs determine EV/HEV sales and the growth potential
- High volume production allows price to fall below 400 USD/kWh
- EV/HEV combined sales predicted to reach 30 % of market by 2025
- Result – production exceeds 30 Million EV/HEV cars per annum by 2025!?



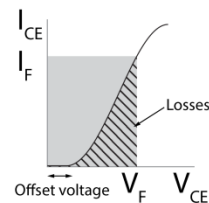
- Light EV/HEV vehicles will constitute 32% of the market by 2025
- Other 'electric vehicle' markets are also expected to be substantial, but diverse
 - Buses: 13%
 - Military: 16%
 - Forklift: 15%



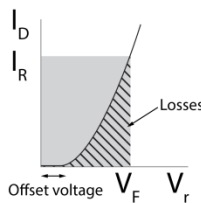
- Strict CO₂ fleet emission pressures are being placed up on the automotive industry
- Critical need to reach 95 gCO₂/km by 2020/2025
- Move to introduce EV/HEV models more rapid than expected



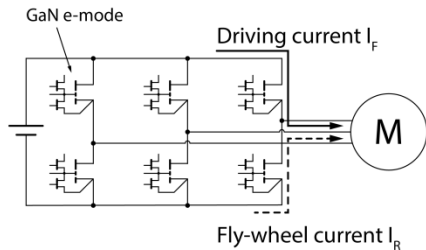
IGBT I-V characteristics



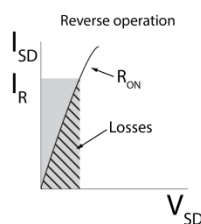
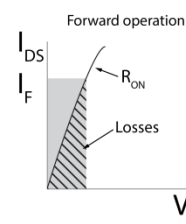
FRD I-V characteristics



$$\text{Losses} = V_F \cdot I_F + V_F \cdot I_R$$



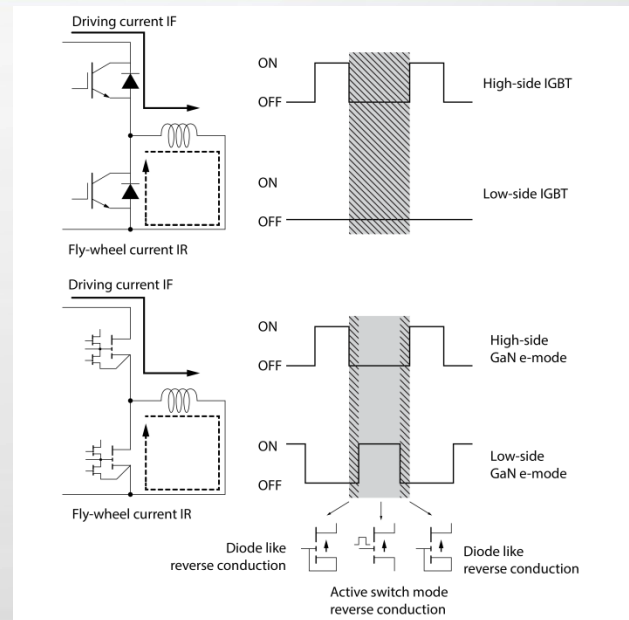
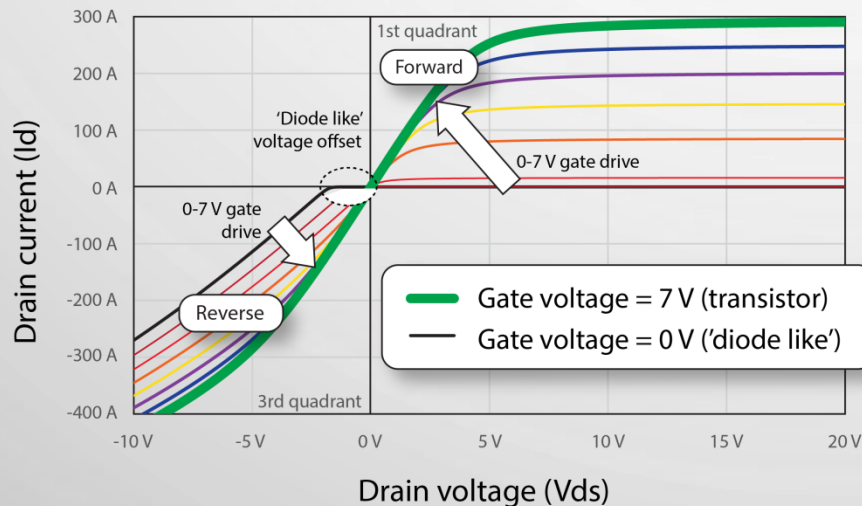
GaN E-mode I-V characteristics



$$\text{Losses} = R_{ON} \cdot I_F^2 + R_{ON} \cdot I_R^2$$

- Traction Inverter Semiconductor Modules account for 30% of total cost of the unit - the Inverter is the second most expensive component after the battery pack
- GaN e-Mode has lower losses due to the absence of the Offset Voltages of the Fast Recovery Diodes and IGBTs
- Lower losses lead to reduced cooling system costs
- GaN e-Mode system allows smaller battery packs to be used

GaN e-Mode forward and reverse conduction



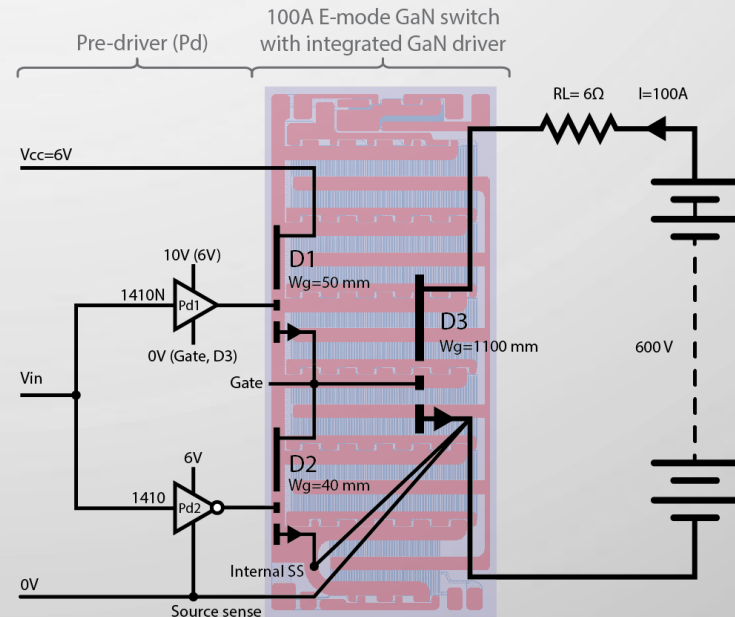
- Reverse conduction is an intrinsic operational capability of an GaN e-Mode – no Fast Recovery Diodes are required
- When the GaN e-Mode active switch mode is used, as shown, very low losses are achieved because the 'diode like' offsets are eliminated

Adopted from: C. Assad, et al. CIPS 2012

25°C, 400A Typ. values	IGBT	GaN/Si Sim.	
V _{on} (V)	1.45	0.4	Voltage drop at full load 400A
P _{on} (W)	580	160	Conduction loss at full load
E _{off} (mJ)	13	0.25	Switching off energy
E _{on} (mJ)	2.9	0.42	Switching on energy
V _F (V)	1.55	0.4	Forward voltage drop (reverse current)
P _{VF} (W)	620	160	Reverse conduction loss
E _{REC} (mJ)	3.6	0.9	Reverse recovery loss
V _{on@ 100A} (V)	1.0	0.1	Voltage @ 25% load
P _{on@ 100A} (W)	100	10	Conduction loss @ 25% load

- IGBT/FRD offset voltage greatly effects losses achieved at typical 100A running current
- Four parallel connected GaN e-Mode devices each 650V/4mΩ provides a 1mΩ on resistance a 10 to 1 improvement in power loss

- The GaN device can be built as a very large integrated single structure whereas the IGBTs usually are paralleled devices within a module which uses an external driver
- The GaN device shown is a 100 A/650 V design that includes an on-chip driver and it includes a yield enhancement scheme
- This device is a first step towards a totally integrated very large 400 A integrated GaN structure





The laminate packaged device shown is a 650 V - 50 m Ω GaN-on-Si e-mode transistor.

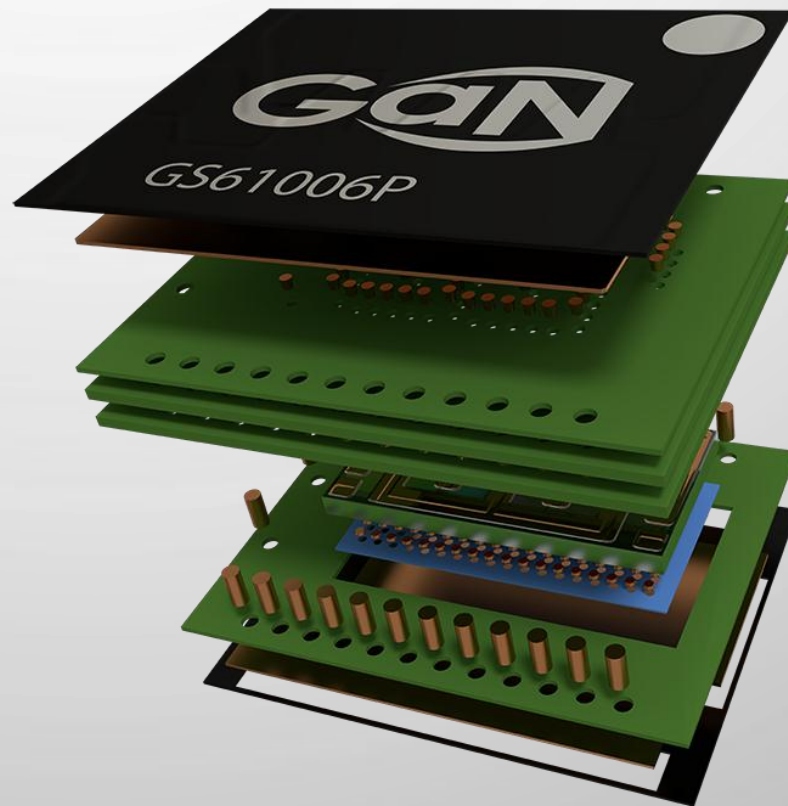
The embedded lateral GaN devices have the smallest parasitic elements and the package interconnect significantly supplements the current carrying capacity of the GaN die.

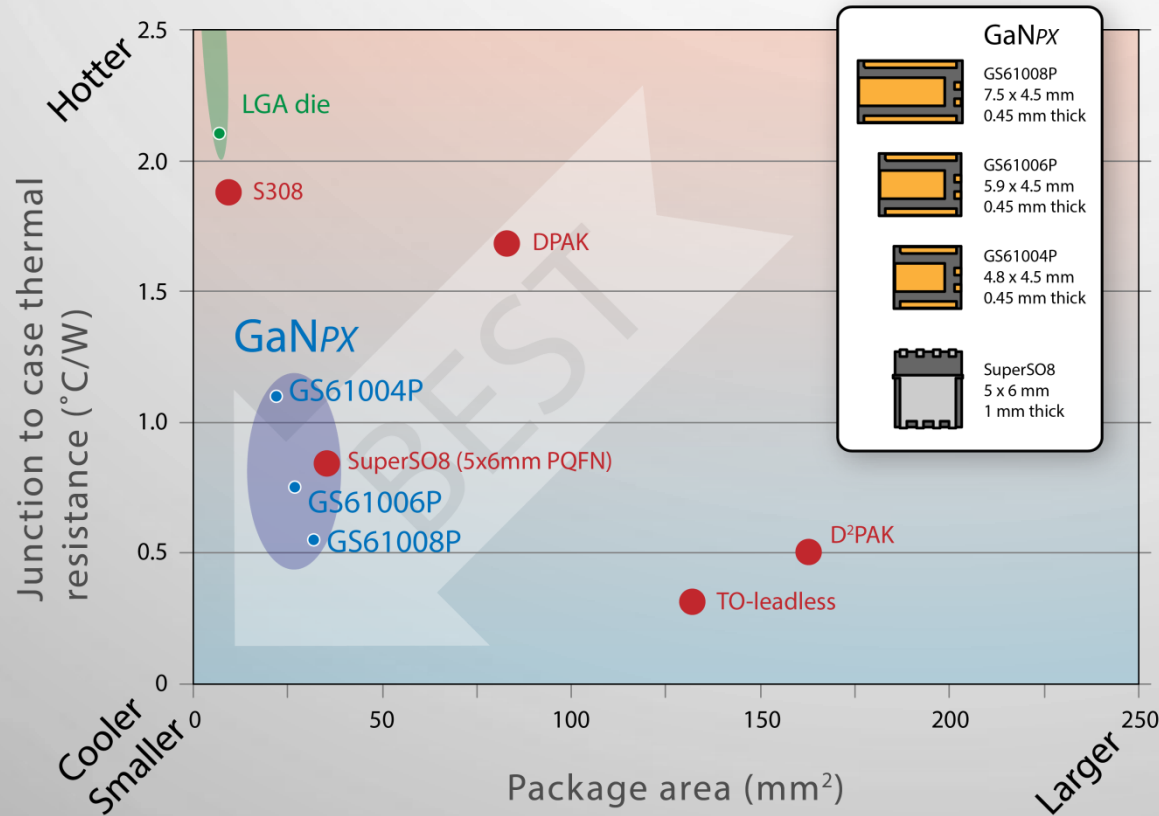
GaN_{PM} embedded packaging cross-section



Superior inductance, current handling, and thermal performance

- The embedding technique has completely removed any electromigration concerns because the package metal augments the RDL and on-chip metal.
- The total metal thickness exceeds 30 microns and the critical width is more than 5 times larger.





Benefits of GaN_{PX} packaging

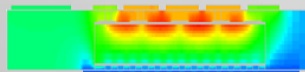
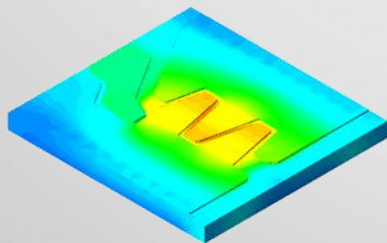
- Superior in terms of area and thermal resistance
- Best package figure of merit (°C/W * mm²)
- Less than half the volume of the SuperSO8

Smaller and provides excellent thermal performance

Bottom-side cooled package comparison



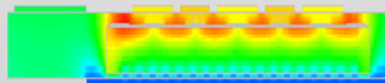
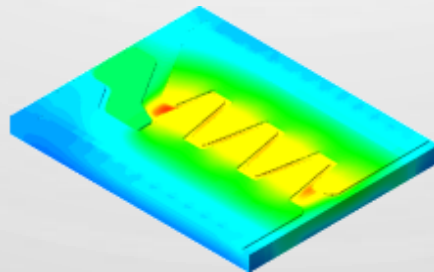
GS61004P
4.8 x 4.5 mm
0.45 mm thick



1.1 °C/W



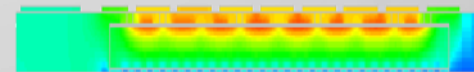
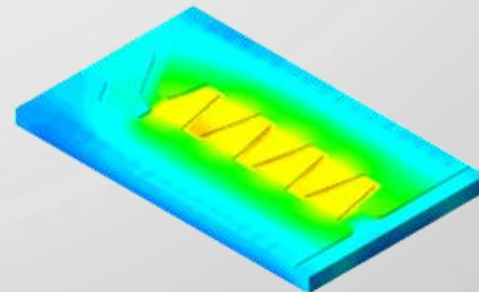
GS61006P
5.9 x 4.5 mm
0.45 mm thick



0.75 °C/W



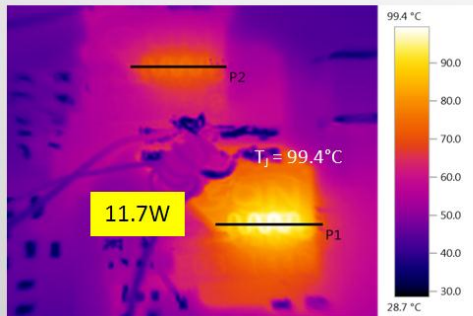
GS61008P
7.5 x 4.5 mm
0.45 mm thick



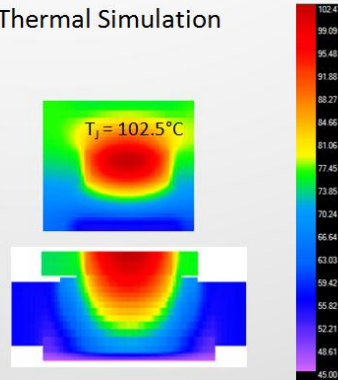
0.55 °C/W

1.0 mm PCB, 228 vias, 2 Cu layers

Measurement

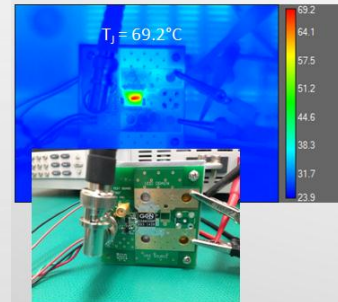


Thermal Simulation

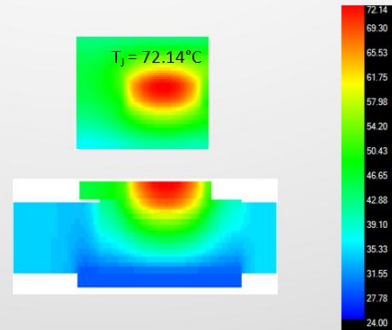


1.6 mm PCB, 123 vias, 4 Cu layers, $P=10\text{ W}$

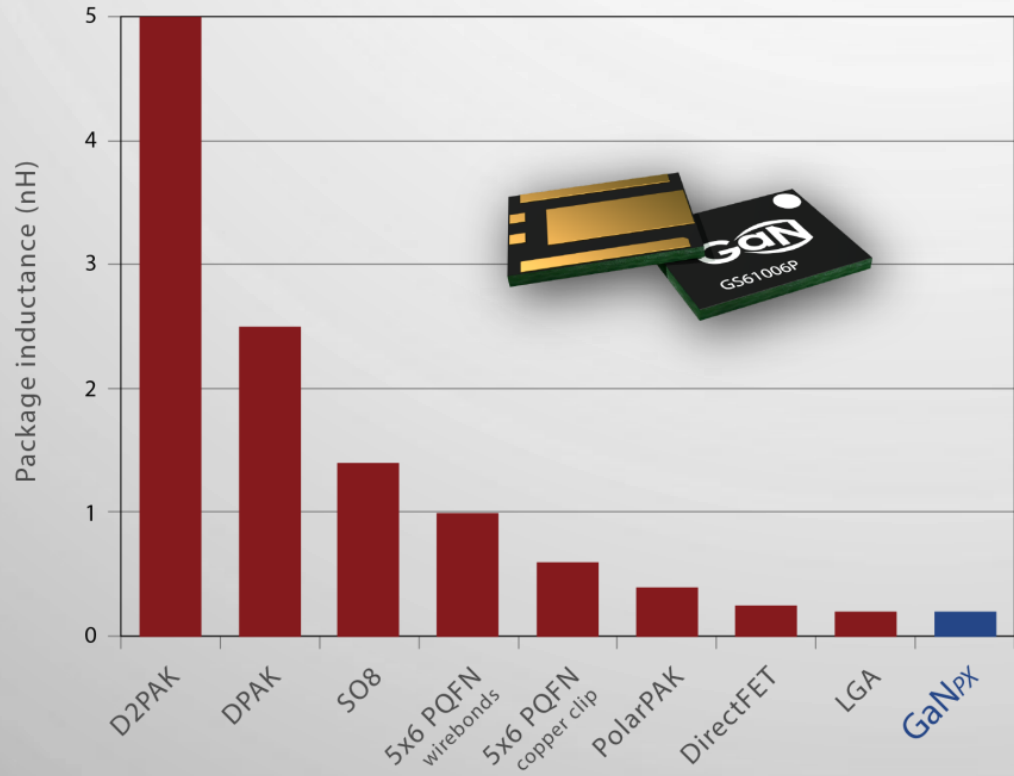
Measurement



Thermal Simulation



- Good agreements between the measurement and the thermal simulation results were obtained
- Thermal simulation predicts slightly higher junction temperature (~4%)
- The thermal camera measures the average temperature, the temperature from thermal simulation is maximum temperature

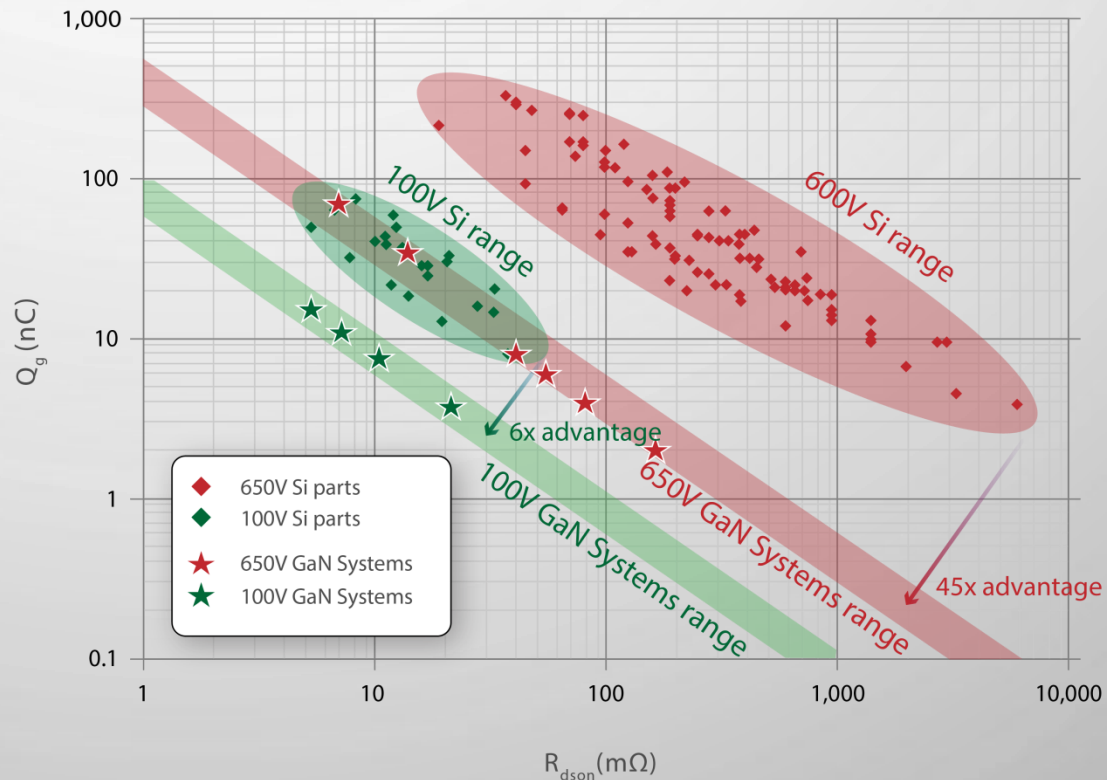


Benefits of low inductance packaging

- Vital requirement for lowest losses
- Lowest EMI
- Minimal voltage overshoot
- Simplifies gate drive
- Faster operation

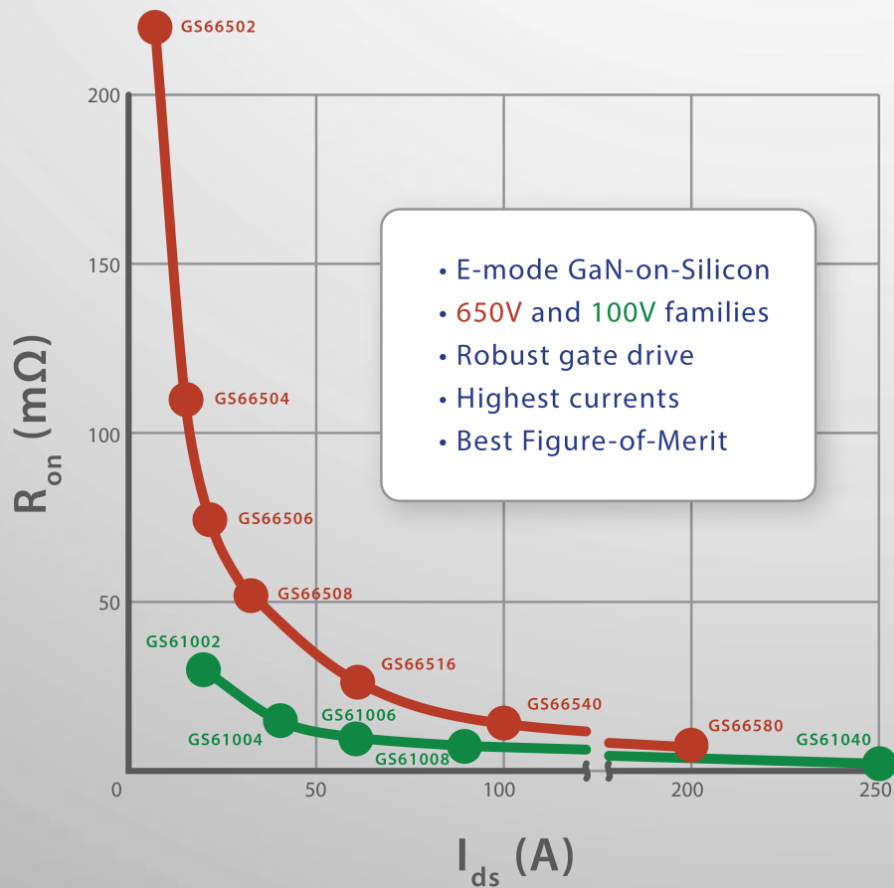
GaNpx inductance is as low as an unpackaged part (LGA)

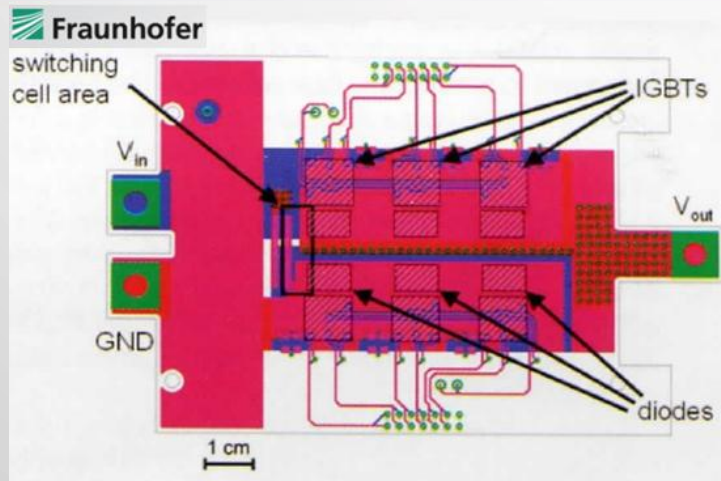
- GaN transistors have lower switching charge requirements than Si MOSFETs for a given specified on-resistance and blocking voltage
- Cascodes and SiC devices have lower performance
- Embedded E-mode devices have superior R_{ON} & Q_G performance



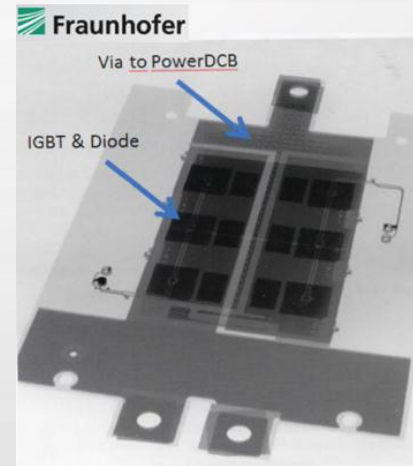
Parameter	GaN e-Mode	GaN Cascode	Si MOSFET	Si/FRD IGBT
FOM: $Q_G \cdot R_{on}$ ($pC \cdot \Omega$)	375	1,400	10,000	17,000
FOM _{HS} : $(Q_{GD} + Q_{GS2}) \cdot R_{on}$ ($pC \cdot \Omega$)	185	550	4,400	7,300
$Q_{RR, DIODE}$ (400A) (nC)	0	2,000	190,000	6,000

1. GaN e-Mode FOM is:
 - 3 - 4 times better than Cascode
 - 25 - 30 times better than MOSFET
 - 40 - 50 times better than FRD/IGBT
2. GaN e-Mode Hard Switching FOM is:
 - 2 - 3 times better than Cascode
 - 20 - 30 times better than MOSFET
 - 30 - 40 times better than FRD/IGBT
3. GaN e-Mode has no diode charge storage losses!





PCB layout 10kW system



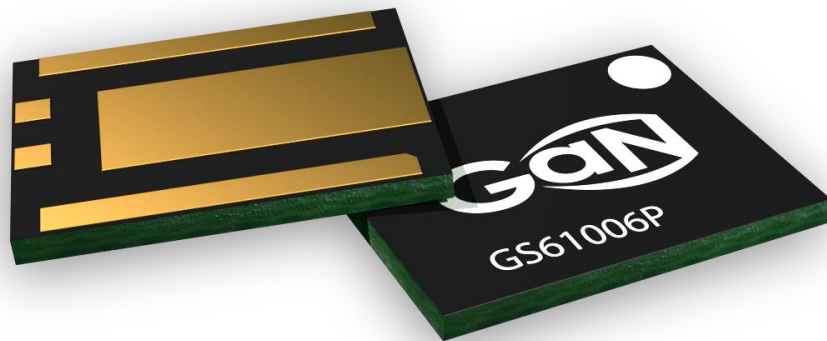
X-ray picture of the 10kW module

- 10kW IGBT Embedded design has forced cooling
- 10kW GaN Embedded design can be finned HS cooled
- Future - Embedded 50kW module

Source: Advancing Microelectronics (IMAPS), JAN/FEB 2015, vol. 42, No.1

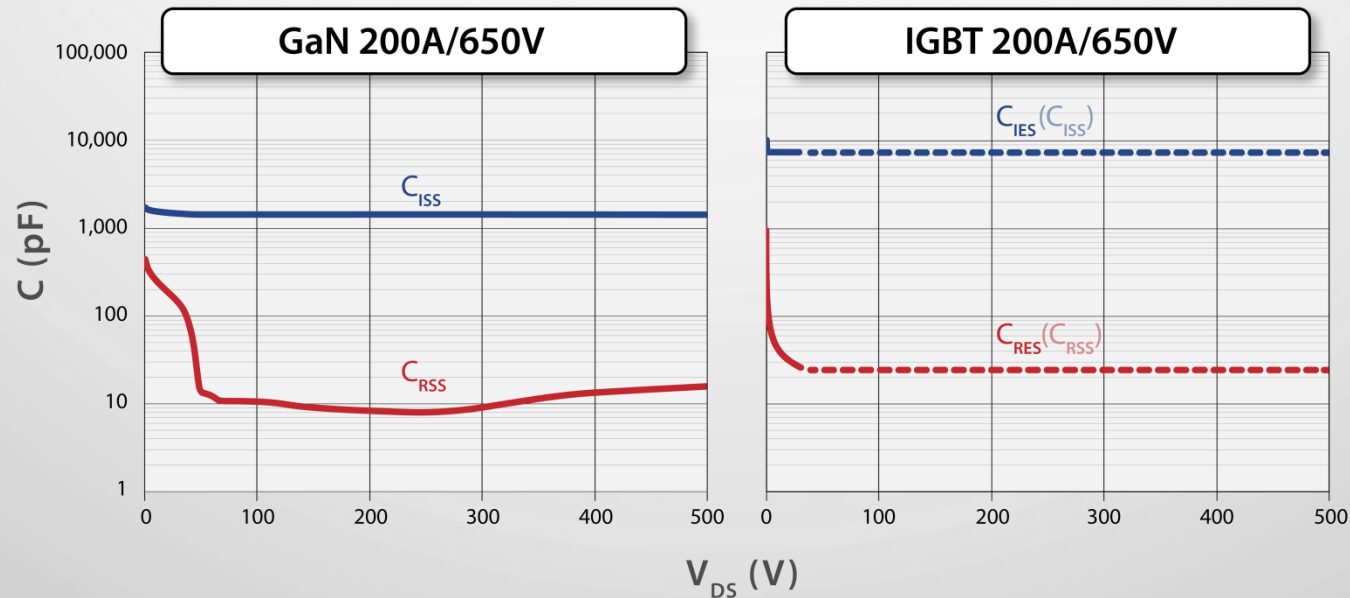
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- Superior in terms of area and thermal resistance
- Best package figure of merit ($^{\circ}\text{C}/\text{W} * \text{mm}^2$)
- GaN_{px} inductance is as low as an unpackaged part (LGA)

Thank you for your attention



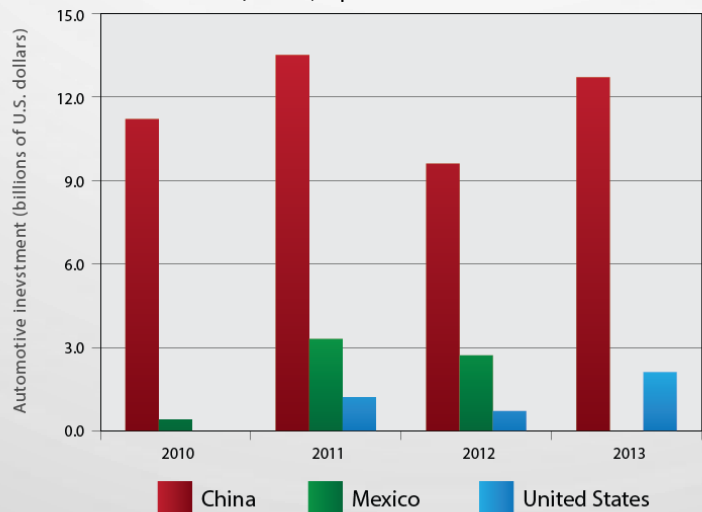
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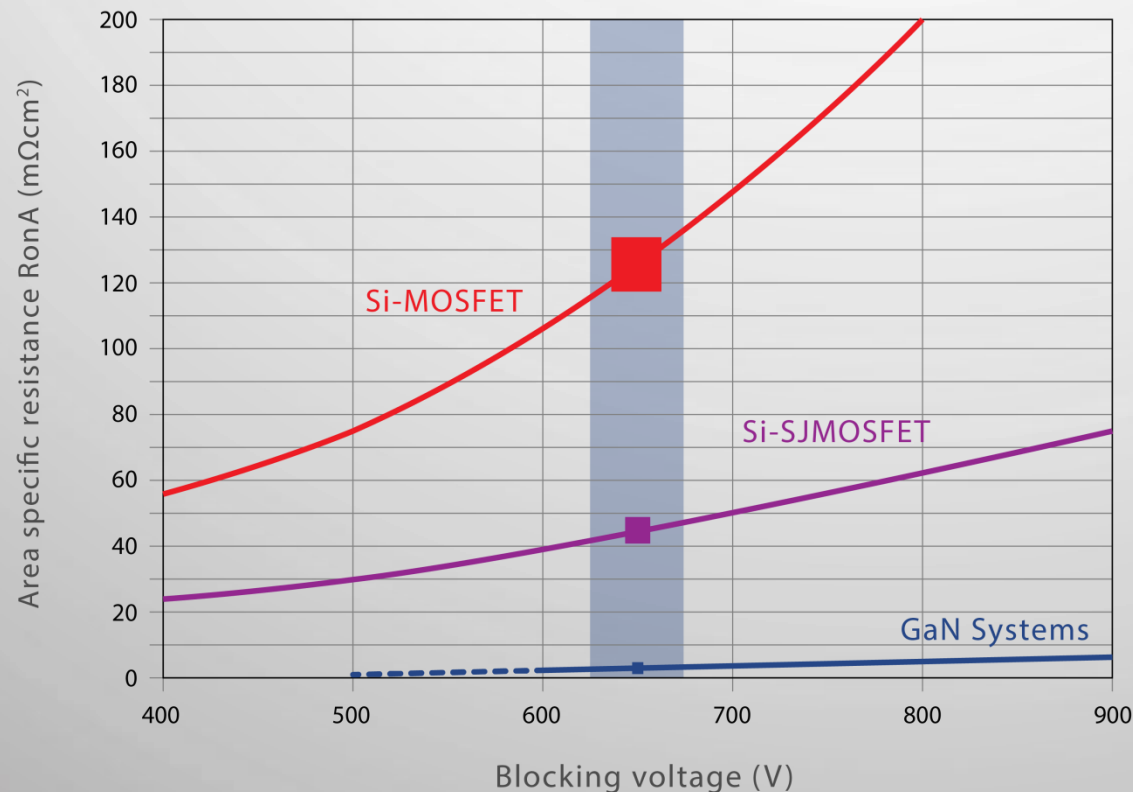
- Capacitances: C_{ISS} - 5 times lower , C_{RSS} - 2 times lower
- Total Gate Charge 40 vs. 300 nC
- Gate Voltage Swing 6 vs. 15 volts
- GaN device has integrated driver

Data: Office of Automotive and Vehicle Research –
Windsor U/G&M, April -2014



- Automaker spent \$17.6 billion (US) around the world in 2013 to increase vehicle-making capacity
- In the past four years China spent \$46.9 billion, Mexico spent \$6.3 billion
- Even before 2010 transportation counted for 27% of total “end-use” energy and road vehicle CO₂ emission reached seven gigatons!!!

650V transistors compared



Chip area ratio



- Chip area typically 40 times, and 15 times, smaller than Si-MOSFETS and Si-SJMOSFETS respectively for the same R_{ON}
- Smaller chip size reduces gate charge Q_G and capacitance